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Applicant:

Yumiko KAWANO, et al.

INFORMATION DISCLOSURE STATEMENT

(Use several sheets if necessary)

Filing Date January 18, 2002 Group

···		T	U.S	PATENT DOCUMENTS			
Examiner Initial		Document Number	Date.	Name	Class	Sub- Class	Filing Date (if appropriate
	AA						
	AB		·.				
	AC						
	AD	·				·	
	AE						
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	AG	<u> </u>					
	AH						
	AI						
			FOREI	GN PATENT DOCUMENTS		, ,	
xaminer		Document				Sub-	TRANSLATIO
ER.	AK	Number	Date	Name	Class	Class	Yes No
7		64-501	01/1989	Japan	-		No
	AL	0349695	01/90	L'Air Liquide			No
	AM	63-072881	04/88	Toshiba Corporation		 	Abstract
	AN	09-186110	07/97	Tokyo Electron			Abstract
	AO	05-078846	03/93	Osaka Gas Co.			Abstract
\(\frac{1}{2} \)	AP	05-226282	09/1993	NEC Corporation			Abstract
EK	AQ	64-068474	09/1989	Tokyo Electron	<u> </u>		Abstract
·1	· 1	OTHER DOC	UMENTS (Inc	luding Author, Title, Date, P	ertinent Page	es, etc.)	· ***
CK	AR	S.C. SUN, et al. "Characterization of Diffusion Barrier Properties of CVD and PVD Tungsten Nitride Thin Films" VMIC Conference, June 18-20, 1996					
EK	AS	Toshiya SUZUKI, et al., "Comparison of CVD TiN, PECVD WNx, and CVD W-Si-N as Upper Electrode Materials for Ta ₂ O ₅ DRAM Capacitors" Conference Proceedings ULSI XIII, 1998					
	ΑТ						
	ER	5 V		DATE CONSIDERI	ap 12 /	120	